

	<b>Hit s</b>	<b>Search Text</b>	<b>DBs</b>
<b>6</b>	114	((resist or photoresist) same pattern) and ((pattern or hole or via or (line near6 space)) same (aspect near5 ratio) same LSI)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>7</b>	10	((resist or photoresist) same pattern) and ((striation or roughness or variation or var\$4) same (resist or photoresist) same (pattern or via or hole) same uneven\$5) and ((pattern or hole or via or (line near6 space)) same (aspect near5 ratio) same LSI)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>8</b>	54	((resist or photoresist) same pattern) and ((resist or photoresist) same (smooth\$4 or cover\$4 or thicken\$5 or enhanc\$4) same (coat\$4 or layer or film)) and etch\$4 and ((pattern or hole or via or (line near6 space)) same (aspect near5 ratio) same LSI)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>9</b>	0	((resist or photoresist) same pattern) and etch\$4 and uniformit\$4 and ((pattern or hole or via or (line near6 space)) same (aspect near5 ratio) same LSI same VLSI)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>10</b>	42	((resist or photoresist) same pattern) and ((pattern or hole or via or (line near6 space)) same (aspect near5 ratio) same LSI) and ((aspect near7 ratio) near20 (VLSI or LSI))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	<b>Hits</b>	<b>Search Text</b>	<b>DBs</b>
<b>11</b>	1	((resist or photoresist) same pattern) and ((pattern or hole or via or (line near6 space)) same (aspect near5 ratio) same LSI same VLSI)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>13</b>	21	((resist or photoresist) same pattern) and ((resist or photoresist) same (smooth\$4 or cover\$4 or thicken\$5 or enhanc\$4 or improv\$4) same (coat\$4 or layer or film)) and (resin same (polyvinyl near5 (aryl or benzyl or phenyl) near5 (acetal or ether or ester)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>14</b>	25	((resist or photoresist) same pattern) and ((resist or photoresist) near16 (coat\$4 or layer or film)) and (resin same (polyvinyl near5 (aryl or benzyl or phenyl) near5 (acetal or ether or ester)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>15</b>	4	S14 NOT S13	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>16</b>	25	((resist or photoresist) same pattern) and (resin same (polyvinyl near5 (aryl or benzyl or phenyl) near5 (acetal or ether or ester)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>17</b>	25	((resist or photoresist) same pattern) and (resin\$4 same (polyvinyl near5 (aryl or benzyl or phenyl) near5 (acetal or ether or ester)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	<b>Hit s</b>	<b>Search Text</b>	<b>DBs</b>
<b>18</b>	32	((resist or photoresist)) and (resin\$4 same (polyvinyl near5 (aryl or benzyl or phenyl) near5 (acetal or ether or ester)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>19</b>	11	S18 NOT S13	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>20</b>	50	((resist or photoresist)) and (resin\$4 same (polyvinyl near16 (aryl or benzyl or phenyl) near15 (acetal or ether or ester)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>21</b>	29	S20 NOT S13	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB